

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L5	30	HCD and polycrystalline silicon	US-PGPUB	ADJ	ON	2009/02/26 07:43
L7	310022	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/26 08:17
L8	254	L7 and (siN or silicon nitride or "si.sub.3n.sub.4") same treat\$4 same repeat\$4	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/26 08:17
L9	84	L8 and (siN or silicon nitride or "si.sub.3n.sub.4") same treat\$4 with repeat\$4	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/26 08:17
S1	309701	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:21
S2	2445	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) and ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:21
S3	448	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) same ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:23
S6	448	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) same ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:50
S9	80	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") with (multi-layer) same ("n.sub.2" or nitrogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:51
S10	45	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") with (multi-layer) same anneal\$3	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:52
S13	104	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") with (multi-layer) and (ammonia or "nh.sub.3") same (treatment or post-treatment or anneal\$3)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:55

S15	13	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") with (multi-layer same (nitrogen or "n.sub.2") with (treatment or post-treatment or anneal \$3)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:56
S19	79	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") with (multi-layer same (treatment or post-treatment or anneal\$3)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 11:26
S20	33	S1 and (multi-layer or multilayer)(siN or silicon nitride or "si.sub.3n.sub.4") with (multi-layer)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 11:30
S21	93	S1 and (multi-layer or multilayer)(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 11:30
S22	7	S21 and (multi-layer or multilayer)(siN or silicon nitride or "si.sub.3n.sub.4") same (treatment or post-treatment or anneal\$3)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 11:30
S23	2	"20080050523"	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 11:46
S24	157	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (hydrogen or "h.sub.2") (plasma or treatment) and (cl or "cl.sup.-" or chlorine or halogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 11:59
S25	7	S24 and (siN or silicon nitride or "si.sub.3n.sub.4") same (hydrogen or "h.sub.2") (plasma or treatment) same (cl or "cl.sup.-" or chlorine or halogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 12:04
S26	16	S24 and (siN or silicon nitride or "si.sub.3n.sub.4") same (hydrogen or "h.sub.2") same (cl or "cl.sup.-" or chlorine or halogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 12:08
S27	9	S26 not S25	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 12:08

S28	7	("2004/0121085").URPN.	USPAT	ADJ	ON	2009/02/25 14:10
S29	309701	(siN or silicon nitride or "si. sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 14:16
S30	732	S29 and (hot wire or hotwire)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 14:16
S31	257	S30 and (hydrogen or "h. sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 14:18

2/26/2009 8:34:40 AM

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